

	Hits	Search Text	DBs
41	8	((coat\$4 or film or form\$4 or layer) same (photoresist or resist or polyimide) same (substrate or wafer or device) same (microlens or non\$4planar or circuit\$4) same spray\$4 same angle)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
42	2	((coat\$4 or film or form\$4 or layer) same (photoresist or resist or polyimide) same (substrate or wafer or device) same (microlens or non\$4planar or circuit\$4)) and ((photoresist or polyimide or photosensitive or resist) near16 spray\$4 near6 (coat\$4 or apply or application or form\$3 or deposit\$4 or layer or dispens\$4) near16 angle)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
43	3	((coat\$4 or film or form\$4 or layer) same (photoresist or resist or polyimide) same (substrate or wafer or device) same (microlens or non\$4planar or circuit\$4)) and ((photoresist or polyimide or photosensitive or resist) near16 spray\$4 near6 (coat\$4 or apply\$3 or application or form\$3 or deposit\$4 or layer or dispens\$4) near16 angle)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
44	9	((coat\$4 or film or form\$4 or layer) same (photoresist or resist or polyimide) same (substrate or wafer or device) same (microlens or non\$4planar or circuit\$4)) and ((photoresist or polyimide or photosensitive or resist) near16 spray\$4 near16 angle)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB